

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Applicant(s): DUBOWSKI, Jan J. et al

Serial No: N/A

Filing Date: Herewith

Examiner: Scott B. Geyer Art Unit: 2829

Title: **Multilayer Microstructures and Laser Based Method
for Precision and Reduced Damage Patterning of Such
Structures**

Docket No: 11261-1A

January 23, 2004

To: The Commissioner of Patents
and Trademarks
Washington, D.C. 20231
U.S.A.

Sir:

PRELIMINARY AMENDMENT

Please amend this application as follows:

IN THE CLAIMS:

Please cancel claims 1-15 and 21.

Please enter new claims 1-5 submitted herewith.

REMARKS

We enclose a copy of the Notice of Allowability in affirmation of the Election
of group 1 1-16 and 21.